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::Abstracts::

Abstracts should be submitted electronically over the web-page by February 15, 2010.

Abstracts should have no more than one page A4 in length. Acceptable file formats are MS Word and Adobe pdf. You may specify whether you would prefer to present your work in the form of a poster or as an oral presentation. The final decision, however, will be made by the scientific committee. You will be notified of the acceptance by March 15, 2010. Please notice that the number of participants is restricted to about 100.

::Proceedings::

Papers of the conference contributions will be published as a special issue of *physica status solidi (c)*. If wanted by the authors and suggested by the referee and the editor, a limited number of the manuscripts can be selected for publishing in a regular issue of *physica status solidi (a)* or *(b)* additionally.



10th International Workshop

BEAM INJECTION ASSESSMENT OF MICROSTRUCTURES IN SEMICONDUCTORS



Halle, Germany

July 4-8, 2010

<http://www.biams2010.de>

First Circular



::About BIAMS::

The BIAMS workshop series was inaugurated in Paris in 1988 and followed by conferences in France, Italy, Spain, Germany, Japan, France, Russia, and Spain. The BIAMS 2010 is the direct follower of the conference held 2008 in Toledo, Spain.

The 10th workshop "Beam Injection Assessment of Microstructures in Semiconductors" will be held in the city of Halle, lying in Saxony-Anhalt (Germany), from July 4 to 8, 2010. The conference venue is the Dorint Hotel Charlottenhof (www.dorint.com/en/hotel-halle-saale), located in the city centre. Participants can book this hotel at a reduced rate.

The BIAMS workshop deals with theoretical and experimental topics related to the assessment of defects and nano- and microstructures in semiconductors by beam injection and related methods. The workshop will provide a forum for exchange between physicists, materials scientists and technologists working in this field.

The conference will be organized in sections with key lectures given by a limited number of invited speakers on topics of relevant scientific and technological interest. Poster sessions will also be held during the conference.

The official language of the conference will be English.

Since this conference is held in the "Solar Valley" region of Germany, the special topic of this conference is the application of beam injection methods to photovoltaic materials and devices. Nevertheless, the conference is open to any kind of beam injection assessment of microstructures in semiconductors.

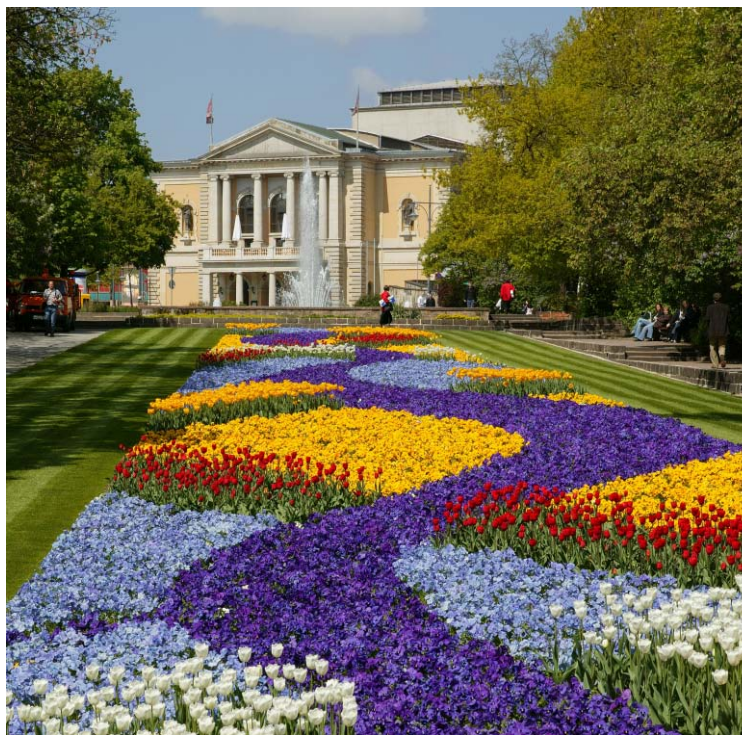
::Main Topics::

Semiconductor characterization methods

- Electron beam characterization methods: cathodoluminescence, EBIC, TEM, STEM, EBSD, ...
- Light characterization methods: spatially resolved PL, microRaman, OBIC, ...
- Scanning probe microscopy: STM, AFM and SNOM techniques
- Ion beams
- Other microscopy characterization techniques

Application of these and related techniques to the study of

- Photovoltaic materials and devices (Special Topic)
- Point and extended defects, impurities, interfaces ...
- Heterostructures, quantum structures, devices ...
- Nanostructures, nanowires ...
- Optical and electronic properties of defects, microstructures and nanostructures in general
- Any quantitative and analytical aspect of local beam injection assessment of semiconductor materials.



::Organizers::

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Max Planck Institute of Microstructure Physics, Halle

Hartmut S. Leipner Co-Chairman
Martin Luther University Halle-Wittenberg

Horst Blumtritt
Max Planck Institute of Microstructure Physics, Halle

Wilfried Erfurth
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Frank Heyroth
Martin Luther University Halle-Wittenberg

Eckhard Pippel
Max Planck Institute of Microstructure Physics, Halle

Peter Werner
Max Planck Institute of Microstructure Physics, Halle

::Deadlines::

February 15, 2010 – Abstract submission

March 31, 2010 – Regular registration

July 5, 2010 – Submission of manuscripts

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